

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Inventor Sujit Sharan
Assignee Micron Technology, Inc.
Priority Group Art Unit 2825
Priority Examiner G. Lee
Attorney's Docket No. MI22-1421
Title: Methods of Forming Silicon Dioxide Layers, and Methods of Forming
Trench Isolation Regions

To: Mail Stop Patent Application
Commissioner for Patents
Art Unit 2825
P.O. Box 1450
Alexandria, VA 22313-1450

From: James E. Lake (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

PRELIMINARY AMENDMENT

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